	19th of November
09:00-09:05	Opening
09:05-09:50	**Prof. Stacey Bent** *Stanford University, Stanford, CA, United States* Molecular Design and Atomic-Scale Control: New Directions in EUV-Photoresist Materials and Pattern Enhancement
09:50-10:20	**Prof. Howard Fairbrother** *Johns Hopkins University, Baltimore, Maryland, USA* Role of Low-Energy Electrons in All-Dry Processing Strategies for Semiconductor Technologies
10:20-10:50	Coffee
10:50-11:20	**Prof. Philip D. Rack** *University of Tennessee, Department of Material Science and Engineering, Knoxville TN, USA* Focused Electron Beam Induced Etching of Superconducting and Semiconducting Materials
11:20-11:40	**Prof. Mattia Fanetti** *Materials Research Laboratory, University of Nova Gorica, Ajdovščina, Slovenia* E-beam local heating with SEM: a new tool for e-beam nanopatterning
11:40-12:00	**Prof. David J. Lewis** *Department of Chemistry, University of Manchester, U.K.* E-Beam Lithography of Topological Insulators: Nanoscale Bismuth(III) Selenide Written Directly from a Single-Source Precursor
12:00-14:00	Lunch & Leisure
14:00-14:20	**Dr. Nenad Bundaleski** *CEFITEC, NOVA University Lisbon, Portugal* Carbon coatings for the electron cloud mitigation in particle accelerators
14:20-14:40	**Prof. Wolfgang S. M. Werner** *TU Wien, Institute of Applied Physics, Vienna, Austria* Electronic doorway states as efficient secondary electron escape channels in layered graphitic materials
14:40-15:00	**Dr. Georghii Tchoudinov** *School of Science and Technology, University of Camerino, Italy* *CNR– Istituto Officina dei Materiali (IOM), Trieste, Italy* Role of the electron Inelastic Mean Free Path in x-ray photoemission and x-ray absorption spectroscopy of solid copper
15:00-15:30	Coffee
15:30-16:00	**Prof. Bo Da** *University of Science and Technology of China, Hefei, P.R. China* Correlated Electron-Matter Interactions: From Inelastic Scattering to Beam Focusing via Rotationally Structured Crystals
16:00-16:20	**Dr. Phay J. Ho** *Argonne National Laboratory, Lemont, IL, USA* Modeling of fundamental mechanisms initiated x-ray irradiation: from atomic to nanometer scales
16:20-16:40	**Dr. Adam Hrdý** *Thermo Fisher Scientific, Brno, Czechia* Chemistry Assisted Delayering of Advanced Semiconductor Devices Using MultiChem
Conference closing	